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Measurements of thermal transport at the nanoscale using kHz and ultrafast thermal waves

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### Outline

- 3ω method
- Time-domain thermoreflectance (TDTR)
- The heatl diffusion equation in not completely valid at high frequencies: frequency dependent thermal conductivity and ballistic phonon transport.

#### $3\omega$ Method

Uses single metal film for heater/thermometer (Birge, 1987); (Cahill, 1990).



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Measure  $\Delta V$  with a bridge circuit and digital lockin amplifier.



Heat flow in a radial coordinate r.

$$\nabla^2 T - q^2 T = 0 \qquad q^2 = \frac{i\omega}{D}; \quad D = \frac{\Lambda}{C}$$
$$\nabla^2 = \frac{1}{r} \frac{\partial}{\partial r} \left( r \frac{\partial}{\partial r} \right).$$

Solution for an infinite half-space

$$\Delta T(r) = \frac{P}{l\pi\Lambda} K_0(qr)$$

 $K_0$  is the zeroth order modified Bessel function Think of this as the circular thermal wave

Take the Fourier transform of this frequency domain solution

$$\Delta T(k) = \int_0^\infty \Delta T(x) \cos(kx) \, dx \,,$$
  
$$\Delta T(k) = (P/2I\Lambda) [1/(k^2 + q^2)^{1/2}] \,.$$

For a low thermal conductivity thin film on a high thermal conductivity substrate

$$\Delta T(\omega) = \Delta T_s + \Delta T_f$$
$$\Delta T_s = \frac{P}{l\pi\Lambda_s} \int_0^\infty \frac{\sin^2(kb)}{(kb)^2(k^2 + q^2)^{1/2}} dk$$
$$\Delta T_f = \frac{Pd}{2Lb\Lambda_f}$$
$$q^2 = \frac{2i\omega}{D_s}$$

(Factor of 2 because current is at frequency  $\omega$ )

•

When |q|b < 0.3

$$\Delta T_s(\omega) = \frac{P}{l\pi\Lambda_s} \left[ \frac{1}{2} \ln\left(\frac{D_s}{b^2}\right) + \eta - \frac{1}{2} \ln(2\omega) - \frac{i\pi}{4} \right]$$

numerically  $|q|b \ll 1$ , gives  $\eta = 0.92$ . Empirically,  $\eta \simeq 1.05$ .



In-phase  $\Delta T$  for a 45 nm SiO<sub>2</sub> film deposited on a Si wafer (Lee, 1996). Curves  $\Delta T_{Si}$  are the calculated response of the substrate.

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### Time-domain thermoreflectance



Clone built at Fraunhofer Institute for Physical Measurement, Jan. 7-8 2008

### Time-domain thermoreflectance



## psec acoustics and time-domain thermoreflectance

- Optical constants and reflectivity depend on strain and temperature
- Strain echoes give acoustic properties or film thickness
- Thermoreflectance gives
   thermal properties





### Schmidt et al., RSI 2008

- Heat supplied by modulated pump beam (fundamental Fourier component at frequency f)
- Evolution of surface temperature



### Schmidt et al., RSI 2008

- Instantaneous temperatures measured by time-delayed probe
- Probe signal as measured by rf lock-in amplifier



Time (a.u.)

### Analytical solution to 3D heat flow in an infinite half-space, Cahill, RSI (2004)

• spherical thermal wave

$$q(r) = \frac{\exp(-qr)}{2\pi\Lambda r} \quad q^2 = (i\omega/D)$$

Hankel transform of surface temperature

$$G(k) = \frac{1}{\Lambda (4\pi^2 k^2 + q^2)^{1/2}}$$

- Multiply by transform of Gaussian heat  $P(k) = A \exp(-\pi^2 k^2 w_0^2/2)$ source and take  $\theta(r) = 2\pi \int_0^\infty P(k)G(k)J_0(2\pi kr) \ k \ dk$ inverse transform
- Gaussian-weighted
   surface temperature

$$\Delta \mathcal{T} = 2\pi A \int_0^\infty G(k) \exp\left(-\pi^2 k^2 \left(w_0^2 + w_1^2\right)/2\right) k \, dk$$

### Iterative solution for layered geometries

$$\begin{pmatrix} B^+ \\ B^- \end{pmatrix}_n = \frac{1}{2\gamma_n} \begin{pmatrix} \exp(-u_n L_n) & 0 \\ 0 & \exp(u_n L_n) \end{pmatrix} \\ \times \begin{pmatrix} \gamma_n + \gamma_{n+1} & \gamma_n - \gamma_{n+1} \\ \gamma_n - \gamma_{n+1} & \gamma_n + \gamma_{n+1} \end{pmatrix} \begin{pmatrix} B^+ \\ B^- \end{pmatrix}_{n+1}$$

$$u_n = \left(4\pi^2 k^2 + q_n^2\right)^{1/2} \qquad q_n^2 = \frac{i\omega}{D_n} \qquad \gamma_n = \Lambda_n u_n$$

$$G(k) = \left(\frac{B_1^+ + B_1^-}{B_1^- - B_1^+}\right) \frac{1}{\gamma_1}$$

### Signal analysis for the rf lock-in

 In-phase and out-of-phase signals by series of sum and difference over sidebands

$$\operatorname{Re}\left[\Delta R_{M}(t)\right] = \frac{dR}{dT} \sum_{m=-M}^{M} \left(\Delta \mathcal{T}(m/\tau + f) + \Delta \mathcal{T}(m/\tau - f)\right) \exp(i2\pi m t/\tau)$$
  
$$\operatorname{Im}\left[\Delta R_{M}(t)\right] = -i \frac{dR}{dT} \sum_{m=-M}^{M} \left(\Delta \mathcal{T}(m/\tau + f) - \Delta \mathcal{T}(m/\tau - f)\right) \exp(i2\pi m t/\tau)$$

 out-of-phase signal is dominated by the *m*=0 term (frequency response at modulation frequency *f*)

### Windows software

#### author: Catalin Chiritescu,

#### users.mrl.uiuc.edu/cahill/tcdata/tdtr\_m.zip

TDTR_M - [Program Status]				
File Moo	lel Help			
Ready 0.62000E-03 0.68000E-03 0.98000E+07 0.80650E+08 4 0.10000E-04 2.0000 2.4200 0.10000E-06 0.10000E-02 0.10000 0.20000E-04 0.50000E-02 1.6000 0.10000 0.55000 1.6000 the arrival time of the pump beam is advanced Calculation started. PLEASE WAIT Calculation Finished **************				
Layer Information				
	Thickness (nm) Therm	al Conductivity (W/cm·K)	Heat Capacity (J/cm^3-K)	
Layer 1		2 0	2.42	
Layer 2	1 C	1e-3	0.1	
Layer 3	200 0	5e-3 C	1.6 C	
Substrate	1.0e6 @	0.55	1.6 C	
			Done	

# Thermoreflectance data for isotopically pure Si

- Two free fitting parameters
  - thermal conductivity, 165 W/m-K
  - AI/Si interface conductance, 185 MW/m<sup>2</sup>-K



Phoenix, Arizoi

## Time-domain Thermoreflectance (TDTR) data for TiN/SiO<sub>2</sub>/Si



### TDTR: early validation experiments



### Thermal conductivity map of a human tooth



Zheng et al., JAP (2008)

## The thermal penetration depth and phonon mean-free-path

 First, make the (incorrect) assumption that the mean-free-path of all phonons is the same.

$$\Lambda = \frac{1}{3}Cv^{2}\tau \qquad l = v\tau$$

$$d = \sqrt{\frac{\Lambda}{\pi fC}} \qquad d = \frac{v}{3}\sqrt{\frac{\tau}{f}} \qquad \frac{d}{l} = \frac{1}{3\sqrt{f\tau}} \gg 1$$

•  $f\tau \ll 1$  so the penetration depth is large compared to the mean-free-path

## In reality, heat is carried by phonons with a broad distribution of mean-free-paths

• Simplest case of thermal conductivity where resistive scattering dominates.

$$\Lambda = \frac{1}{3} \int_0^{\omega_c} c(\omega) v_g^2(\omega) \tau(\omega) d\omega$$

 $c(\omega)$  = heat capacity of phonon mode

 $v_g(\omega) =$  phonon group velocity

 $\tau(\omega)$  = scattering time

 $\omega_c$  = cut-off frequency

#### Make a "Klemens-like" calculation

• Assume linear dispersion for  $\omega < \omega_c$  and  $\tau^{-1} \propto \omega^2 T$ 

$$\Lambda = \frac{A}{T} \int_0^{\omega_c} d\omega = \frac{A}{T} \omega_c$$

• Convert to an integral over mean-free-path  $l = \frac{B}{\omega^2 T}$ 

$$\Lambda = \frac{A\sqrt{B}}{2T^{3/2}} \int_{l_c}^{\infty} \frac{1}{l^{3/2}} dl$$
$$\frac{\Lambda(l_{\text{max}})}{\Lambda} = 1 - \left(\frac{l_c}{l_{\text{max}}}\right)^{1/2}$$

 $\ell_{\rm c}$  is the mean-free-path at the cut-off frequency  $\ell_{\rm max}$  is the maximum mean-free-path that contributes to  $\Lambda$ 

## Heat is carried by phonons with a broad distribution of mean-free-paths

- Phonon scattering by charge carriers or boundaries will narrow the distribution.
- Alloying and point defects will broaden the distribution.
- Relaxational damping will eventually be a limiting factor.
- Details are probably important (scattering rates, normal processes, dispersion...)



### Thermoreflectance raw data at t=100 ps

- fix delay time and vary modulation frequency *f*.
- semiconductor alloys show deviation from fit using a single value of the thermal conductivity
- Change in V<sub>in</sub> doesn't depend on *f*. V<sub>out</sub> mostly depends on  $(f\Lambda C)^{-1/2}$



Koh *et al.*, PRB (2007)



Koh *et al.*, PRB (2007) *f* (MHz)

## How can thermal conductivity be frequency dependent at only a few MHz?

- $2\pi f\tau \ll 1$  for phonons that carry significant heat. For dominant phonons,  $\tau \sim 100$  ps, and  $2\pi f\tau \sim 10^{-3}$ .
- But the thermal penetration depth d is not small compared to the dominant mean-free-path l<sub>dom</sub>.

$$\mathbf{d} = \sqrt{\Lambda / \pi C f}$$

- Ansatz: phonons with *l*(ω) > d do not contribute to the heat transport in this experiment.
- True only if the "single-relaxation-time approximate" fails strongly. For single relaxation time  $\tau$ ,  $\ell$ <<d because  $f\tau$  << 1.

### Frequency and thickness dependence for InGaP and InGaAs

• h=film thickness; d = thermal  $d = \sqrt{\Lambda / \pi C f}$ penetration depth



#### Differentiate to get a distribution function



### Current open question: why don't we see frequency dependence in pure crystals?

$$\Lambda = \frac{1}{3} \int_0^{\omega_c} c(\omega) v_g^2(\omega) \tau(\omega) d\omega$$

$$C(\omega) \propto \omega^2$$

$$v_g(\omega) =$$
 phonon group velocity

$$\tau(\omega) = (A\omega^2 T)^{-1}$$

 $\omega_c$  = cut-off frequency for heat carrying acoustic modes

$$\omega_{\rm D}$$
 = Debye frequency

 Fraction of thermal conductivity from phonons with mean-freepath smaller than the thermal penetration depth

$$\phi = 1 - \left(\frac{\omega_D^3 f \tau_c}{\omega_c^3}\right)^{1/4}$$

## Current open question: why don't we see frequency dependence in pure crystals?

• Make an order-of-magnitude estimate

$$\left(\frac{\omega_D}{\omega_c}\right)^3 \sim 10; \ f \approx 10 \text{ MHz}; \quad \tau_c \sim 10 \text{ ps}; \ f \tau_c \sim 10^{-4}$$
$$\implies \phi = 0.82$$

- This reduction is not observed.
- Why are pure crystals different than the alloy?
- Do we need to replace the diffusion equation as the basis for the analysis of TDTR experiments? (see also experiments by Minnich and Chen)
- Boundary conditions at the metal/sample interface are complicated. Too many unknowns (?). What experiment and theory can provide more constraints?